

Acetone
CMOS



Material No.: 9005-68
Batch No.: 0000023354
Manufactured Date: 2012/10/26
Retest Date: 2017/10/25

Certificate of Analysis

| Test | Specification | Result |
|---|---------------|--------|
| Assay ((CH ₃) ₂ CO) (by GC, corrected for water) | >= 99.5 % | 99.9 |
| Color (APHA) | <= 10 | 5 |
| Residue after Evaporation | <= 5 ppm | 1 |
| Titration Acid (µeq/g) | <= 0.3 | 0.3 |
| Titration Base (µeq/g) | <= 0.5 | 0.1 |
| Water (H ₂ O) | <= 0.5 % | 0.1 |
| Solubility in H ₂ O | Passes Test | PT |
| Chloride (Cl) | <= 0.2 ppm | < 0.1 |
| Phosphate (PO ₄) | <= 0.05 ppm | < 0.05 |
| Trace Impurities - Aluminum (Al) | <= 50.0 ppb | < 5.0 |
| Arsenic and Antimony (as As) | <= 5 ppb | < 5 |
| Trace Impurities - Barium (Ba) | <= 20.0 ppb | < 1.0 |
| Trace Impurities - Beryllium (Be) | <= 10.0 ppb | < 1.0 |
| Trace Impurities - Bismuth (Bi) | <= 20.0 ppb | < 10.0 |
| Trace Impurities - Boron (B) | <= 10.0 ppb | < 5.0 |
| Trace Impurities - Cadmium (Cd) | <= 10.0 ppb | < 1.0 |
| Trace Impurities - Calcium (Ca) | <= 25.0 ppb | 2.0 |
| Trace Impurities - Chromium (Cr) | <= 10.0 ppb | < 1.0 |
| Trace Impurities - Cobalt (Co) | <= 10.0 ppb | < 1.0 |
| Trace Impurities - Copper (Cu) | <= 10.0 ppb | < 1.0 |
| Trace Impurities - Gallium (Ga) | <= 10.0 ppb | < 1.0 |
| Trace Impurities - Germanium (Ge) | <= 10.0 ppb | < 10.0 |
| Trace Impurities - Gold (Au) | <= 20.0 ppb | < 5.0 |
| Trace Impurities - Iron (Fe) | <= 20.0 ppb | < 1.0 |

| Test | Specification | Result |
|---|---------------|--------|
| Trace Impurities – Lead (Pb) | <= 10.0 ppb | < 10.0 |
| Trace Impurities – Lithium (Li) | <= 10.0 ppb | < 1.0 |
| Trace Impurities – Magnesium (Mg) | <= 20.0 ppb | < 1.0 |
| Trace Impurities – Manganese (Mn) | <= 10.0 ppb | < 1.0 |
| Trace Impurities – Molybdenum (Mo) | <= 10.0 ppb | < 5.0 |
| Trace Impurities – Nickel (Ni) | <= 10.0 ppb | < 5.0 |
| Trace Impurities – Niobium (Nb) | <= 50.0 ppb | < 1.0 |
| Trace Impurities – Potassium (K) | <= 10.0 ppb | < 10.0 |
| Trace Impurities – Silicon (Si) | <= 50.0 ppb | < 10.0 |
| Trace Impurities – Silver (Ag) | <= 10.0 ppb | < 1.0 |
| Trace Impurities – Sodium (Na) | <= 10.0 ppb | < 5.0 |
| Trace Impurities – Strontium (Sr) | <= 10.0 ppb | < 1.0 |
| Trace Impurities – Tantalum (Ta) | <= 50.0 ppb | < 5.0 |
| Trace Impurities – Thallium (Tl) | <= 10.0 ppb | < 5.0 |
| Trace Impurities – Tin (Sn) | <= 20.0 ppb | < 10.0 |
| Trace Impurities – Titanium (Ti) | <= 10.0 ppb | < 1.0 |
| Trace Impurities – Vanadium (V) | <= 10.0 ppb | < 1.0 |
| Trace Impurities – Zinc (Zn) | <= 20.0 ppb | < 1.0 |
| Trace Impurities – Zirconium (Zr) | <= 10.0 ppb | < 1.0 |
| Particle Count – 0.5 µm and greater (Rion KS42AF) | <= 100 par/ml | 5 |
| Particle Count – 1.0 µm and greater (Rion KS42AF) | <= 8 par/ml | 3 |

For Microelectronic Use

Country of Origin: US
 Packaging Site: Paris Mfg Ctr & DC



Phillipsburg, NJ 9001:2008, 14001:2004
 Paris, KY 9001:2008
 Mexico City, Mexico 9001:2008
 Deventer, The Netherlands 9001:2008, 14001:2004, 13485:2003
 Gliwice, Poland 9001:2008, 17025:2005
 Selangor, Malaysia 9001:2008
 Dehradun, India, 9001:2008, 14001:2004, 13485:2003
 Mumbai, India, 9001:2008, 17025:2005
 Panoli, India 9001:2008



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